

PATENTS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of
Pierre COLOMBET et al.

Serial No. (unknown)

Filed herewith

CEMENT COMPOSITION, ITS USE FOR
THE PRODUCTION OF A SELF-LEVELING
LIQUID CASTING, AND A CASTING THUS
OBTAINED

#5
HWO
4502



INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
Washington, D.C. 20231
Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the accompanying documents, copies of which are attached to this statement, are made of record on the enclosed sheet.

A concise explanation of the relevance of these items is that these references were cited by the French Patent Office in the corresponding French application Serial No. 00.13117, filed October 13, 2000.

Respectfully submitted,

YOUNG & THOMPSON

By

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PATENT AND TRADEMARKATTY. DOCKET NO.
C 98-0138.2

SERIAL NO.

OFFICE

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(Use several sheets if necessary)

(37 CFR 1.98(b))

APPLICANT
Pierre COLOMBET et al.FILING DATE
October 15, 2001

GROUP

**U.S. PATENT DOCUMENTS**

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

		DOCUMENT NO.	PUBL. DATE	COUNTRY OR PATENT OF- FICE	CLASS	SUB CLASS	TRANSLATION YES NO
	AJ	DE 39 09 070	09/90	Germany			no
	AK	FR 2 780 396	12/99	France			no
	AL	11157898	06/99	Japan			abstract only
	AM						
	AN						

OTHER DOCUMENTS (Including Author, Title, Date, Relevant Pages, Place of Publication)

	AO	
	AP	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered.
Include copy of this form with next communication to applicant.